

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Substitute for form PTO-1449

Sheet 1 of 1

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|------------------------|--------------------|
| Application Number | 10/799,073 |
| Filing Date | 12 March 2004 |
| First Named Inventor | Michel Luc Cote |
| Art Unit | 1756 |
| Examiner Name | Stephen B. Rosasco |
| Attorney Docket Number | NMTI 1002-26 |

U.S. PATENT DOCUMENTS

| Examiner's Initials | | Patent No. Number-Kind Code | Pub. Date MM-DD- YYYY | Name | Pages, Cols, Lines of Relevant Passages or Figures |
|------------------------|----|--------------------------------|-----------------------------|--------|--|
| <i>SL</i> | A1 | US 6,040,892 | 03-21-2000 | Pierat | |
| | A2 | US | | | |
| | A3 | US | | | |
| | A4 | US | | | |
| | A5 | US | | | |
| | A6 | US | | | |
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FOREIGN PATENT DOCUMENTS

| Examiner's Initials | | Patent No. Number-Kind Code | Pub. Date MM-DD-YYYY | Name | Pages, Cols, Lines of Relevant Material | T |
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| | B2 | | | | | |
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| | B4 | | | | | |
| | B5 | | | | | |
| | B6 | | | | | |

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

| Examiner's Initials | | Include name of the author (in CAPITAL LETTERS), title of article, title of item (book, magazine, journal, serial, symposium, etc), date, page(s), volume-issue number(s), publisher, city and/or country where published. | T |
|------------------------|----|--|---|
| <i>SL</i> | C1 | Jinbo et al. "0.2um Or Less i-Line Lithography By Phase-Shifting Mask Technology" IEEE, pp. 33.3.1-33.3.4 (1990). | |
| | C2 | | |
| | C3 | | |
| | C4 | | |

Examiner
Signature*S. Rosasco*Date
Considered*3/28/07*

פ' י' טו"ב (תג-טז)

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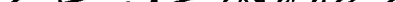
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| Sheet | 1 | of | 1 |
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| Application Number | 10/799,073 |
| Filing Date | 12 March 2004 |
| First Named Inventor | Michel Luc Cole |
| Art Unit | 1756 |
| Examiner Name | Unassigned |
| Attorney Docket Number | NMT1 1002-26 |

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|--------------------|---|----------------|---------|
| Examiner Signature |  | Date Completed | 3/28/07 |
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|---|---|--------------------------|--------------------|------------------------|--------------|
| Substitute for form 1449B/PTO | | Complete if Known | | | |
| INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary) | | Application Number | 10/799,073 | | |
| | | Filing Date | 12 March 2004 | | |
| | | First Named Inventor | Michel Cote et al. | | |
| | | Group Art Unit | unknown | | |
| | | Examiner Name | unknown | | |
| Sheet | 1 | of | 3 | Attorney Docket Number | NMTI 1002-26 |

| OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS | | | |
|---|----------|---|----------------|
| Examiner Initials | Cite No. | Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. | T ² |
| | C1 | SAKATA, MIWA, et al., "A Novel Radiation Sensitive Spin-on-glass Convertible into SiO2 and the Simple Fabrication Process Using It," 26 July 1993* (*ATI Bell Labs fax date), 3 pages. | |
| | C2 | PISTOR, THOMAS V., "Rigorous 3D Simulation of Phase Defects in Alternating Phase-Shifting Masks," Proceedings of SPIE 4562-1038 (March 2002), 13 pages | |
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| Examiner Signature | | Date Considered | 3/28/07 |
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| | | | First Named Inventor | Michel Cote et al. | |
| | | | Group Art Unit | unknown | |
| | | | Examiner Name | unknown | |
| Sheet | 2 | of | 3 | Attorney Docket Number | NMTI 1002-26 |

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| Examiner Initials ¹ | Cite No. ² | Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. | T ² |
| AR | | SUGAWARA, MINORU, et al., "Defect printability study of attenuated phase-shifting masks for specifying inspection sensitivity," Proc. SPIE 2621-49, September 1995, 16 pages. | |
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| Examiner Signature | <i>A. Zoraco</i> | Date Considered | 3/28/07 |
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| OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS | | | |
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| AB | | SUZUKI, AKIYOSHI, et al., "Multilevel imaging system realizing k1=0.3 lithography," Proc. SPIE 3679-36, March 1999, 13 pages. | |
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| Filing Date | 12 March 2004 |
| First Named Inventor | Michel Luc Cote |
| Art Unit | 1756 |
| Examiner Name | Unassigned |
| Attorney Docket Number | NMTI 1002-26 |

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Examiner
Signature

A. Zivase

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